

09-05-00

A

Please type a plus sign (+) inside this box → ☐

Approved for use through 09/30/2000. OMB 0651-0032
Patent and Trademark Office: U.S. DEPARTMENT OF COMMERCE

Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it displays a valid OMB control number.

UTILITY PATENT APPLICATION TRANSMITTAL

(Only for new nonprovisional applications under 37 C.F.R. § 1.53(b))

Attorney Docket No.	MTI-31046
First Inventor or Application Identifier	Donald L. Yates
Title	See 1 in Addendum
Express Mail Label No.	EL700461001US

APPLICATION ELEMENTS

See MPEP chapter 600 concerning utility patent application contents.

ADDRESS TO: Assistant Commissioner for Patents
Box Patent Application
Washington, DC 20231

- ☒ * Fee Transmittal Form (e.g., PTO/SB/17)
(Submit an original and a duplicate for fee processing)
- ☒ Specification [Total Pages 28]
(preferred arrangement set forth below)
 - Descriptive title of the Invention
 - Cross References to Related Applications
 - Statement Regarding Fed sponsored R & D
 - Reference to Microfiche Appendix
 - Background of the Invention
 - Brief Summary of the Invention
 - Brief Description of the Drawings (if filed)
 - Detailed Description
 - Claim(s)
 - Abstract of the Disclosure
- ☒ Drawing(s) (35 U.S.C. 113) [Total Sheets 1]
1
- Oath or Declaration [Total Pages 3]
1
 - ☒ Newly executed (original or copy)
 - ☐ Copy from a prior application (37 C.F.R. § 1.63(d))
(for continuation/divisional with Box 16 completed)
 - ☐ DELETION OF INVENTOR(S)
Signed statement attached deleting inventor(s) named in the prior application, see 37 C.F.R. §§ 1.63(d)(2) and 1.33(b).

- ☐ Microfiche Computer Program (Appendix)
- Nucleotide and/or Amino Acid Sequence Submission (if applicable, all necessary)
 - ☐ Computer Readable Copy
 - ☐ Paper Copy (identical to computer copy)
 - ☐ Statement verifying identity of above copies

ACCOMPANYING APPLICATION PARTS

- ☒ Assignment Papers (cover sheet & document(s))
- ☐ 37 C.F.R. § 3.73(b) Statement of Power of Attorney (when there is an assignee)
- ☐ English Translation Document (if applicable)
- ☒ Information Disclosure Statement (IDS)/PTO-1449 ☒ Copies of IDS Citations
- ☐ Preliminary Amendment
- ☒ Return Receipt Postcard (MPEP 503)
(Should be specifically itemized)
- ☐ * Small Entity Statement(s) filed in prior application (PTO/SB/09-12) Status still proper and desired
- ☐ Certified Copy of Priority Document(s) (if foreign priority is claimed)
- ☒ Other: Power of Attorney by Assignee & Certificate

* NOTE FOR ITEMS 1 & 13 IN ORDER TO BE ENTITLED TO PAY SMALL ENTITY FEES, A SMALL ENTITY STATEMENT IS REQUIRED (37 C.F.R. § 1.27), EXCEPT IF ONE FILED IN A PRIOR APPLICATION IS RELIED UPON (37 C.F.R. § 1.28).

16. If a CONTINUING APPLICATION, check appropriate box, and supply the requisite information below and in a preliminary amendment:

<input type="checkbox"/> Continuation	<input type="checkbox"/> Divisional	<input type="checkbox"/> Continuation-in-part (CIP)	of prior application No. _____
Prior application information: Examiner _____		Group / Art Unit: _____	

For CONTINUATION or DIVISIONAL APPS only: The entire disclosure of the prior application, from which an oath or declaration is supplied under Box 4b, is considered a part of the disclosure of the accompanying continuation or divisional application and is hereby incorporated by reference. The incorporation can only be relied upon when a portion has been inadvertently omitted from the submitted application parts.

17. CORRESPONDENCE ADDRESS

<input checked="" type="checkbox"/> Customer Number or Bar Code Label	022202	or <input type="checkbox"/> Correspondence address below
(Insert Customer No. or Attach bar code label here)		

Name					
Address					
City	State	Zip Code			
Country	Telephone	Fax			

Name (Print/Type)	Kristine M. Strodthoff	Registration No. (Attorney/Agent)	34259
Signature	Kristine M. Strodthoff	Date	31-AUG-2000

Burden Hour Statement: This form is estimated to take 0.2 hours to complete. Time will vary depending upon the needs of the individual case. Any comments on the amount of time you are required to complete this form should be sent to the Chief Information Officer, Patent and Trademark Office, Washington, DC 20231. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Assistant Commissioner for Patents, Box Patent Application, Washington, DC 20231.

Attachment to PTO/SB/05 (4/98) Utility Patent Application Transmittal

1. Compositions for Dissolution of Low-K Dielectric Films, and Methods of Use

COMPOSITIONS FOR DISSOLUTION OF LOW-K DIELECTRIC FILMS,
AND METHODS OF USE

FIELD OF THE INVENTION

The present invention relates to compositions and methods for their use in cleaning or etching of wafers used in the fabrication of semiconductor devices. More particularly, the invention relates to compositions for selectively removing low-k dielectric layers and/or photoresist layers on the wafers while controlling the rate of removal of the material, and methods using the compositions.

BACKGROUND OF THE INVENTION

Many semiconductor processes require wafer measurements to be made from time to time for production-line quality control, product stability, and conformance to specifications. Generally, the processing results are evaluated after each significant step. Since many tests are destructive or will harm the product wafer, the measurements are typically performed on a test or “dummy” wafer, which are blank wafers that are mixed in with the product wafers. Dummy wafers are specially prepared to have similar characteristics as the product wafers. Typically, a dummy wafer is made of silicon, although other alternative materials have been described. Since silicon wafers are expensive, when the processing and testing is completed, the dummy wafers are usually cleaned, inspected, and reused. In the recovery or recycling of dummy wafers, it is important to provide a clean surface for subsequent processing. In the recycling of dummy wafers used in a masking photoresist process, it is important to completely remove blanket films of oxide and resist layers from the surface of the wafer down to the bare silicon.

Wet chemical processing is conventionally used for cleaning the surfaces of wafers. The cleaning is performed in order to produce a wafer having a silicon surface that is hydrophobic and repels water as the wafer is pulled out of the bath. The wafers are then rinsed in deionized water, dried in heated nitrogen gas (N_2), and transferred to a processing operation, or stored.

Aqueous mixtures of hydrogen peroxide (H_2O_2) and sulfuric acid (H_2SO_4) are commonly used to strip or remove photoresist from a wafer surface after an etch processing step, or to remove a misaligned resist pattern from a wafer for re-imaging after development and inspection ("rework"). In such applications, it is desirable that the layer that is present under the resist, including, for example, silicon dioxide, remains intact on the wafer surface. In such cases, it is important to quickly remove the photoresist layer without attacking the underlying material. However, organic components in an underlying low-k dielectric layer, can alter the selectivity of the dielectric material to a resist layer.

In other applications, it is desirable to completely remove the oxide layer from a silicon surface. Hydrofluoric acid (HF) is conventionally used as a component of oxide etchants. HF solutions provide selective etch rates of about 100:1 or better for $SiO_2:Si$, and effectively etch away the oxide but not the underlying silicon wafer material. Prevalent HF solutions include, for example, a 1:10 mixture of 49% hydrofluoric acid (HF) and water, and a dilute 1:6 aqueous mixture of HF and ammonium fluoride (NH_4F). However, wet HF chemistries have difficulty removing low-k dielectrics such as a TMS-based low-k dielectric film, largely due to organic components in the oxide films. As a result, cleaning with an HF solution can leave the wafer with a gummy organic residue on the surface.

Therefore, it would be desirable to provide an improved composition for dissolution of low-k dielectric films from silicon-comprising surfaces. It would also be desirable to provide a cleaning composition that will completely remove low-k dielectric and photoresist components from the surface of a substrate such as a dummy wafer. It would also be desirable to provide a composition that can be modified to provide removal of a low-k dielectric material such as a TMS-based low-k dielectric film, from a wafer surface over a range of removal rates according to the application at hand.

SUMMARY OF THE INVENTION

The present invention provides a cleaning composition for use in wet cleaning or etching of a wafer surface, and a method of cleaning or etching wafer surfaces by applying the composition.

The cleaning composition is an aqueous solution that includes one or more effective amounts (v/v) of one or more fluorine-comprising compounds and one or more compatible acids to achieve the desired selectivity to resist and/or a low-k dielectric, and the desired rate of removal of the low-k material and/or the resist. A preferred composition according to the invention is an aqueous solution consisting essentially of the one or more fluorine-comprising compounds and the one or more acids.

The cleaning composition can be modified according to the invention to provide removal of a low-k dielectric material from the surface of a semiconductor wafer or other substrate over a range of removal rates according to the application at hand. In particular, the fluorine-comprising compound and the amount that is used, and also the amount of the acid component that is used, can be varied according to the invention to provide rapid removal of a low-k dielectric material and/or organic materials such as photoresist from the surface of the wafer at a rate of removal of greater than about 1000 angstroms per minute, or to provide controlled removal of either or both of those materials from the wafer surface at a slow to moderate rate of removal of about 50 to about 1000 angstroms per minute. The composition of the invention is useful in removing low-k dielectrics including, for example, trimethylsilane- and dimethylsilane-based low-k dielectrics.

For example, the composition can be formulated for use in a processing step such as a post-etch cleaning where it is desirable to remove low-k dielectric material at a slow and controlled rate so as to provide better process control. In that case, the cleaning composition is formulated with a relatively dilute concentration of the fluorine-comprising compound. By comparison, in a dummy recycling operation after a photoresist deposition or etching step, it is highly desirable to quickly and completely remove the low-k dielectric material and any photoresist or other organic components that may be present from the surface of the wafer, whereby the surface of the wafer is hydrophobic and water sheets off the surface of a wafer. In that case, a relatively high concentration of fluorine-comprising component is used in the composition. The composition can also be formulated to remove photoresist from a wafer, for example, after a mask operation, and leave the underlying low-k dielectric layer intact.

Suitable fluorine-comprising compounds are those that will speciate or ionize to provide fluoride ions at about pH 3 to 9. The fluorine-comprising compound can be an inorganic fluoride compound such as hydrofluoric acid (HF) and ammonium fluoride (NH₄F), or an organic fluoride compound such as tetramethylammonium fluoride and hydrogen fluoride pyridinium. Combined with the inorganic fluorine-comprising compound is an organic acid component that can be one or more of a monobasic, dibasic or tribasic organic acid, and is preferably citric acid, acetic acid, ascorbic acid, or mixtures thereof. An organic fluorine-comprising compound, when used, is combined with an inorganic acid such as sulfuric acid, among others. The acid component is included in an amount to control the pH of the composition at about 3 to about 9.

The invention also provides a method of cleaning a surface of a wafer. One embodiment of the method includes providing an aqueous cleaning composition that includes at least one fluorine-comprising compound and at least one acid component, and has a pH of about 3 to about 9; providing a wafer having a low-k dielectric layer and an overlying photoresist layer on at least one surface; and contacting the surface of the wafer having the low-k dielectric material and photoresist layers thereon with the cleaning solution under conditions effective to remove both of the low-k dielectric material and the photoresist layers substantially completely from the surface of the wafer, at a desired rate of removal whereby the resulting cleaned surface of the wafer is hydrophobic and water sheets off the surface of the wafer.

Another embodiment of the method includes providing an aqueous cleaning composition that includes at least one fluorine-comprising compound and at least one acid component and has a pH of about 3 to about 9; providing a wafer having a masked or unmasked low-k dielectric material on at least one surface; and contacting the surface of the wafer having the low-k dielectric material thereon with the cleaning solution under conditions effective to remove at least a portion of the low-k material at a desired rate of removal.

A further embodiment of the method includes providing an aqueous cleaning composition that includes at least one fluorine-comprising compound and at least one acid, and has a pH of about 3 to about 9; providing a wafer having a low-k dielectric layer and an overlying photoresist layer on at least one surface; and contacting the surface of the wafer having

the low-k dielectric and photoresist layers thereon under conditions effective to remove the photoresist layer at a desired rate of removal while leaving the a low-k dielectric layer essentially intact.

BRIEF DESCRIPTION OF THE PREFERRED EMBODIMENTS

Preferred embodiments of the invention are described below with reference to the following accompanying drawings which are for illustrative purposes only. Throughout the following views, reference numerals will be used on the drawings, and the same reference numerals will be used throughout the several views and in the description to indicate same or like parts.

FIGS. 1A-1B are general illustrations of cross-section of a wafer having a layer of a low-k dielectric material and an overlying photoresist layer on a surface, before and after cleaning, respectively, to remove both layers from the surface of the wafer in accordance with one embodiment of the method of the present invention.

FIGS. 2A-2B are general illustrations of cross-section of a wafer having a layer of an unmasked low-k dielectric material on a surface, before and after cleaning, respectively, to remove the low-k dielectric layer in accordance with another embodiment of the method of the present invention.

FIGS. 3A-3B are general illustrations of cross-section of a wafer having a layer of low-k dielectric material and an overlying photoresist layer on a surface, before and after cleaning, respectively, to remove the photoresist layer from the wafer in accordance with another embodiment of the method of the present invention.

DETAILED DESCRIPTION OF THE PREFERRED EMBODIMENTS

The invention provides improved cleaning of a wafer surface in the production of semiconductor wafers. Aqueous blends of at least one fluorinated compound and at least one compatible acid are provided that can be optimized by task for removal of low-k dielectric material and photoresist or other organic components from the surface of a wafer.

In accordance with the present invention, the compositions can be formulated to provide rapid removal of a low-k dielectric material, a controlled low to moderate rate of removal of a low-k dielectric material, removal of both resist and low-k dielectric materials, and/or removal of photoresist material with selectivity to low-k dielectric material. The blends are used for removal of a low-k dielectric layer and/or a layer of photoresist or other organic layer with selectivity to an underlying layer of a silicon substrate.

The fluorine-comprising compound which attacks the low-k dielectric material, is combined with an acid component that assists in the dissolution of the organic components. The pH of the cleaning composition is maintained at an appropriate level by the addition of an effective amount of the acid component to provide an environment for speciation of the fluorine-comprising compound to fluoride ions, and to achieve the desired etch selectivity. At a pH >9, free fluorine is available only as fluoride ions (F^-) which has little etching effect on silicon oxide material. At a pH <3, the available fluorine species are dominantly molecular, i.e., HF and H_2F_2 . At an about pH 3.5, there is a mixture of species present. Preferably, the pH of the composition is maintained at a pH of about 3 to about 9 such that the ionic fluorine species dominates. By adjusting the pH, the dominant species of fluorine (HF_2^-) in the cleaning composition can be varied to adjust the etch rate on the low-k dielectric material.

Suitable fluorine-comprising compounds are those that speciate and release fluoride ions at a pH between about 3 to about 9. Examples of suitable fluorine-comprising compounds, i.e., include inorganic fluorines such as hydrofluoric acid (HF), ammonium fluoride (NH_4F), and mixtures thereof; and organic fluorines such as tetramethylammonium fluoride, hydrogen fluoride pyridinium, triethylamine trihydrofluoride, and other straight, branched, cyclic or aromatic derivatives, and mixtures thereof.

In the use of HF, NH_4F , or other inorganic fluorine-comprising compound, the acid component is an organic acid. Suitable organic acids include, but are not limited to monobasic acids such as formic, acetic, propionic, n-butyric, isobutyric, and benzoic acid; dibasic acids such as ascorbic, gluconic, malic, malonic, oxalic, succinic, and tartaric acids; tribasic acids such as citric and gallic acids; and mixtures thereof. In the use of an organic fluorine-comprising compound, a suitable inorganic acid is used, as for example, sulfuric acid, hydrochloric acid,

nitric acid and phosphoric acid. The composition is typically in the form of a solution, and includes a solvent, preferably water, for dilution of the components.

The cleaning composition includes the fluorine-comprising compound and acid component in an amount effective to provide the desired selectivity and etch rate for removal of low-k dielectric material and/or a polymeric photoresist. Combinations of various inorganic/organic fluorine-comprising compounds and organic/inorganic acids according to the invention can be used for the desired results.

A first embodiment of a cleaning composition according to the invention and a method for its use in cleaning or etching the surface of a semiconductor wafer, is described with reference to **FIGS. 1A-1B**.

Referring to the figures, a portion of a wafer 10 is shown prior to cleaning (**FIG. 1A**) and after cleaning (**FIG. 1B**). The wafer 10 includes a substrate 12, for example, a silicon substrate, with a surface 14. A layer or film of a low-k dielectric material 16 overlies the surface 14 of the substrate 12. Overlying the low-k dielectric layer 12 are portions of an organic component 18 such as photoresist mask.

According to the invention, a cleaning composition can be formulated to provide complete removal of the photoresist layer 18 and low-k dielectric layer 16 from the surface 14 of the silicon substrate 12. **FIG. 1B** depicts the portion of the wafer 10 after cleaning, with the low-k dielectric layer 16 and the photoresist layer 18 having been completely removed by the cleaning process, resulting in a hydrophobic, oxide-free silicon surface 14.

The substantially complete removal of both a low-k dielectric material and a photoresist layer is particularly useful in the recycling of wafer dummies where it is desired to completely remove all low-k dielectric and organic materials including a photoresist layer from the wafer down to bare silicon to produce a clean surface that is hydrophobic (i.e., water sheets off the surface), for reuse of the wafer dummy in production.

A useful cleaning composition according to the invention for the substantially complete removal of a low-k dielectric material and a photoresist layer or other organic material from the surface of a silicon-comprising semiconductor wafer is an aqueous solution that includes an

inorganic fluorine-comprising compound such as HF, NH₄F, and mixtures thereof, and an organic acid such as citric acid, among others.

An example of a preferred composition to remove substantially all of a low-k dielectric material and a layer of photoresist or other organic material from the surface of a wafer at a relatively low to moderate controlled rate of removal of about 50-1000 angstroms per minute to produce a hydrophobic wafer surface, comprises an aqueous solution of an about 1:2 (v/v) ratio of hydrofluoric acid (HF) and 50 % citric acid and/or other organic acid, or about 30 to about 40 % by volume of 49% HF and about 60 to about 70 % by volume 50% citric acid and/or other organic acid, based on the total volume of the composition, with a pH of about 3 to about 4, to provide a relatively moderate rate of removal of the dielectric and photoresist layers at about 400 to about 600 angstroms per minute. Another useful composition comprises an aqueous solution of an about 2:1 ratio (v/v) of 40 % ammonium fluoride (NH₄F) and 50 % citric acid and/or other organic acid, or about 60 to about 70 % by volume of 40% NH₄F and about 30 to about 40 % by volume of 50% citric acid and/or other organic acid, based on the total volume of the composition, with a pH of about 4 to about 6, to provide a relatively low rate of removal of the low-k dielectric layer at about 50 to about 150 angstroms per minute, preferably about 100 angstroms per minute.

To provide rapid removal of low-k dielectric material at a rate greater than about 1000 angstroms per minute, preferably greater than about 2000 angstroms per minute, and minimal removal of a photoresist layer, a preferred composition is an aqueous solution of 49 % hydrofluoric acid (HF) and 50 % citric acid and/or other organic acid in a ratio (v/v) of about 2:1, or about 63 to about 70 percent by volume of 49% HF and about 30 to about 36 percent by volume of 50% citric acid and/or other organic acid, with a pH of about 2 to about 5, to generally achieve a removal rate of about 2300-2700 angstroms per minute. Another useful composition for fast removal of a low-k material comprises an aqueous solution of 40 % ammonium fluoride (NH₄F) and 50 % citric acid and/or other organic acid in a ratio (v/v) of about 2:1, or about 63 to about 70 percent by volume of 40% NH₄F and about 30 to about 36 percent by volume of 50% citric acid and/or other organic acid, with a pH of about 3 to about 6.

A cleaning composition for substantially complete removal of both a low-k layer and photoresist layer can also be prepared with an organic fluoride such as hydrogen fluoride pyridinium combined with an inorganic acid such as sulfuric acid. A preferred composition comprises an about 1:5 ratio (v/v) of hydrogen fluoride pyridinium and 90 % sulfuric acid (H₂SO₄), and/or other inorganic acid, or about 13 to about 19 % by volume hydrogen fluoride pyridinium and about 80 to about 86 % by volume of 90% H₂SO₄ and/or other inorganic acid, to provide a rapid rate of removal of the photoresist layer and a rate of removal of the dielectric layer at about 700 angstroms per minute.

A second embodiment of a cleaning composition according to the invention, and a method for its use is described with reference to **FIGS. 2A-2B**. The wafer 30 to be cleaned includes a substrate 12, for example, a silicon substrate, and a surface 14. Overlying the surface 14 of the substrate 12 is an unmasked low-k dielectric film or layer 16 having a thickness T₁. According to the method, the cleaning composition is applied to the wafer 30 for removal of at least a portion of the low-k dielectric layer 36 from the surface 34 of the silicon-comprising substrate 32. **FIG. 2B** depicts the portion of the wafer 30 after cleaning. As depicted, the thickness T₁, of the low-k dielectric layer 36 has been reduced to thickness T₂ by the removal process. The low-k dielectric layer 36 can also be completely removed to produce a hydrophobic, oxide-free silicon surface 34, as depicted in **FIG. 1B**.

The foregoing cleaning compositions can be formulated according to the invention to provide removal of at least a portion of the low-k dielectric layer 16 from the surface of a semiconductor wafer at a rapid rate of removal (>1000 angstroms per minute) or a more controlled low to moderate rate of removal (about 50 to about 1000 angstroms per minute). A slow and controlled removal of low-k dielectric films is desirable in cases where removing the low-k dielectric material too quickly from the wafer leads to inadequate process control and causes difficulty in process integration. This is important when the objective is to remove small amounts of the low-k dielectric, such as from a silicon contact area. For example, in a post-etch cleaning, it is desirable to selectively remove a low-k dielectric material from a wafer at a slow and controlled rate in order to remove a small amount of the dielectric material from an etched

feature and leave the bulk of the film intact. In that case, a preferred etchant composition is one that is formulated with a dilute HF ratio.

The compositions can be used to selectively remove all or a portion of a masked low-k dielectric layer while leaving the photoresist mask essentially intact. Such a composition is useful where wet patterning is required (rather than RIE). The composition is formulated to provide an etch selectivity ratio of about 50:1 to about 1000:1 for a low-k dielectric:photoresist whereby the low-k dielectric material is selectively removed without attacking the photoresist or other organic material.

Another embodiment of a cleaning composition according to the invention, and a method for its use to remove photoresist from a wafer surface while leaving an underlying low-k dielectric layer essentially intact on the wafer surface, is described with reference to **FIGS. 3A-3B**. A portion of a wafer 40 is shown which includes a substrate 12, for example, a silicon substrate, with a surface 14. A layer or film of a low-k dielectric material 16 overlies the surface 14 of the substrate 12. Overlying the low-k dielectric layer 16 are portions of a photoresist mask 18. According to the method, a cleaning composition is applied to a wafer 40 to provide selective removal of substantially all of the photoresist mask layer 18, while leaving the underlying layer of low-k dielectric layer 16 essentially intact. **FIG. 2B** depicts the portion of the wafer 40 after cleaning, with the photoresist layer 18 having been completely removed by the cleaning process with the low-k dielectric material remaining on the wafer substrate 12.

This cleaning method is particularly useful for removing a photoresist layer after an etch processing step, or in a rework application to remove a misaligned resist mask. The composition is formulated to provide an etch selectivity ratio of about 200:1 for a low-k dielectric:photoresist in which the photoresist material is selectively removed at about 200 angstroms/minute without substantially attacking the low-k dielectric material, or a rate of removal of up to about 1 angstrom/minute.

A useful composition for the sole removal of a photoresist mask layer or other organic layer overlying a low-k dielectric layer comprises an aqueous solution of an inorganic fluorine-comprising compound and a major amount of an organic acid such as a 50% citric acid, with a pH of about 3 to about 4. A preferred composition comprises an about 1:100 (v/v) of an

inorganic fluorine-comprising compound and an about 20 to about 60 %, preferably about 40 % to about 50 %, aqueous solution of an organic acid. Preferably, the inorganic fluorine-comprising compound is included in an amount of up to about 2 % by volume, preferably about 0.5 % to about 1.5 % by volume, and the organic acid is included in an amount of up to about 99.5 % by volume, preferably about 98.5 % to about 99.5 % by volume, based on the total volume of the composition, with a pH of about 3 to about 3.5. A preferred composition comprises an about 1:100 ratio of 49 % HF and 50 % citric acid and/or other organic acid, which provides a rate of removal of the photoresist layer at about 400-600 angstroms per minute with an etch selectivity for a low-k material relative to a polymeric photoresist material of at least about 200:1.

To clean a wafer surface according to the invention, the wafer is placed in contact with an appropriately formulated cleaning composition to remove the desired layer or layers at a desired rate of removal. The cleaning composition can be applied using a conventional wet chemical application technique as known and used in the art. For example, one or more wafers can be placed vertically in a carrier or boat and then submerged in a recirculating bath of the cleaning composition, with or without agitation for about 5-10 minutes, depending on the thickness of the layer to be removed. The cleaning composition can also be sprayed onto the surface of the wafer. Preferably, a substantially constant concentration of the reactive components of the cleaning composition is brought into contact with the wafer surface so that a uniform rate of removal can be maintained to allow for process uniformity and the desired extent and completeness of removal.

In the cleaning of a wafer, the cleaning composition can be used at a temperature of about 15°C. to about 30°C., preferably at about 15°C. to about 30°C. High temperatures of about 40 to about 60° C. can be typically used to achieve faster etch rates. In a selective removal of a photoresist mask or other organic material and not a low-k dielectric layer, it is preferred that lower temperatures of about 15°C. to about 30°C. are used to improve the selectivity of the low-k dielectric material over the photoresist.

Depending on the composition of the cleaning composition, other selective etch ratios/rates are within the scope of the present invention. The selectivity and removal time can

be adjusted and controlled by varying the concentrations of the fluorine-comprising compound and the acid component, as further illustrated in the examples. The selectivities vary as the v/v ranges increase and decrease. Generally, a composition formulated to comprise a major amount of HF will provide a high etch of the low-k dielectric material selective to the resist. With a major amount of the acid component and a lower content of the fluorine-comprising compound, good removal of the resist selective to the low-k dielectric material will be achieved.

The following examples are given to illustrate specific preferred embodiments of the present invention. Numerous other variations, however, are within the scope of the present invention.

EXAMPLE

This example studies the effect of varying the fluorine-comprising component (49%HF or 40% NH₄F), and the v/v ratios of the fluorine-comprising component and the acid component (50% citric acid) on the rate of removal of a low-k dielectric and a photoresist layer (OIR 897-10I) from a silicon wafer surface.

TABLE 1

Run #	Fluorine component	Parts (v)	Acid Component	Parts (v)	Low-k removal rate (Å/min.)	Photoresist Removal
1	49% HF	100	----	----	^a negligible	^a negligible
2	49% HF	100	----	----	^b negligible	^b negligible
3	40% NH ₄ F	2	50% citric acid	1	100	negligible
4	49% HF	2	50% citric acid	1	2500	negligible
5	49% HF	1	50% citric acid	2	500	complete
6	49% HF	1	50% citric acid	100	Negligible	complete
7 ^c	Hydrogen fluorine pyridinium (anhydride)	1	90% sulfuric acid	5	Complete (700)	Complete

- a Repeated acid/water dips over 30 minutes, produced non-uniform flaking without dissolution of the low-k dielectric or photoresist.
- b A single, prolonged immersion (20 + minutes) showed little or no effect on removal of the low-k or 10i photoresist.
- c The wafer surface had a 3000 angstrom layer of trimethylsilane (TMS) only (no photoresist layer).

The surface of the wafers had a layer of chemical vapor deposited (CVD) trimethylsilane-based low-k dielectric film (TMS delivered in H_2 and N_2O) about 3000 angstroms thick, and an overlying layer of photoresist. The wafers were immersed in a beaker of the cleaning solution. Run Nos. 3-6 were immersed in solution for multiple tests, from 30 seconds to 4 minutes. The low-k dielectric removal rates were determined by using a UV1250 spectroscopic ellipsometer.

The results show that changing the fluorine-comprising component, and varying the amounts of the fluorine and acid components alters the rate of removal of a layer of low-k from the wafer surface.

The results of Run Nos. 1-2 show that HF used alone was ineffective in removing dielectric and photoresist material from the wafer surface. The use of HF alone resulted in pieces of the TMS-based low-k dielectric film and photoresist flaking off and floating on the surface of the cleaning solution, without significant dissolution.

The results of Runs 3 and 4 show the effect of varying the inorganic fluorine component that is used on the rate of removal of the TMS-based low-k dielectric layer. A 2:1 of NH_4F :citric acid provided a low-k dielectric removal rate of about 100 angstroms per minute, while a 2:1 of HF: citric acid provided a low-k dielectric removal rate of about 2500 angstroms per minute.

The results of Run Nos. 4-6 show the effect of varying the weight ratio of the organic acid (50% citric acid) and the fluorine component (HF) on the rate of removal of the TMS-based low-k dielectric film and a polymeric photoresist mask layer from the surface of the wafer. A 1:100 HF: citric acid ratio resulted in complete removal of the photoresist while leaving the low-k layer intact on the surface of the wafer. A 1:2 HF: citric acid ratio resulted in complete removal of both the photoresist and the TMS-based low-k dielectric film layers, with a moderate rate of removal of the low-k layer at about 500 angstroms per minute. A 2:1 ratio of HF: citric acid ratio

WHAT IS CLAIMED IS:

1. A method of cleaning wafer surfaces, comprising the steps of:
providing a wafer surface bearing overlying material thereon; and
cleaning the wafer surface by removing at least a portion of the overlying material from the wafer surface by applying an aqueous solution comprising a major amount of one or more inorganic fluorine-comprising compounds and one or more organic acids in a ratio of about 100:1 to about 55:45, the solution having a pH of about 3 to about 9, such that the surface of the wafer is rendered substantially hydrophobic.
2. The method of Claim 3, wherein the overlying material on the surface of the wafer comprises a low-k dielectric layer, and the step of cleaning the wafer surface comprises removing the dielectric layer at a rate of greater than about 1000 angstroms per minute.
3. The method of Claim 2, wherein the aqueous solution comprises one or more hydrofluoric acid and one or more organic acids in a ratio of about 2:1 (v/v), such that the dielectric layer is removed at a rate of about 2500 angstroms per minute.
4. The method of Claim 2, wherein the aqueous solution comprises at least ammonium fluoride and one or more organic acids in a ratio of about 2:1 (v/v).
5. The method of Claim 1, wherein the overlying material on the surface of the wafer comprises a low-k dielectric layer, and the step of cleaning the wafer surface comprises removing the dielectric layer from the wafer surface at a rate of about 50 to about 1000 angstroms per minute.
6. The method of Claim 5, wherein the aqueous solution comprises at least hydrofluoric acid and one or more organic acids in a ratio of about 1:2 (v/v), such that the dielectric layer is removed at a rate of about 400 to about 600 angstroms per minute.

7. The method of Claim 5, wherein the aqueous solution comprises at least ammonium fluoride and one or more organic acids in a ratio of about 2:1, such that the dielectric layer is removed at a rate of about 50-150 angstroms per minute.
8. The method of Claim 1, wherein the overlying material on the surface of the wafer comprises a low-k dielectric layer, and a photoresist layer overlying the dielectric layer and the step of cleaning the wafer surface comprises removing the dielectric layer and the photoresist layer at a rate of about 50 to about 1000 angstroms per minute.
9. The method of Claim 8, wherein the aqueous solution comprises at least hydrofluoric acid and one or more organic acids in a ratio of about 1:2 (v/v), such that the dielectric layer is removed at a rate of about 400 to about 600 angstroms per minute.
10. The method of Claim 9, wherein the aqueous solution comprises at least ammonium fluoride and one or more organic acids in a ratio of about 2:1 (v/v), such that the dielectric layer is removed at a rate of about 100 angstroms per minute.
11. The method of Claim 1, wherein the composition is an aqueous solution consisting essentially of the one or more inorganic fluorine-comprising compounds and the one or more organic acids.
12. A method for surface treating wafer surfaces, comprising the steps of:
providing a wafer surface having a low-k dielectric layer disposed thereon and a photoresist layer overlying the dielectric layer; and
treating the wafer surface to remove at least a portion of the dielectric layer with minimal removal of the photoresist layer, by applying an aqueous solution of one or more inorganic fluorine-comprising compounds and one or more organic acids, the solution having a pH of about 3 to about 9, such that the dielectric layer is removed selective to the photoresist at a rate of greater than about 1000 angstroms per minute.

13. The method of Claim 12, wherein the aqueous solution comprises at least hydrofluoric acid and the one or more organic acids in a ratio of about 2:1 (v/v), such that the dielectric layer is selectively removed at a rate of about 2300 to about 2700 angstroms per minute.

14. The method of Claim 12, wherein the aqueous solution comprises at least ammonium fluoride and the one or more organic acids in a ratio of about 2:1 (v/v).

15. A method for surface treating wafer surfaces, comprising the steps of:
providing a wafer surface having a low-k dielectric layer disposed thereon and a photoresist layer overlying the dielectric layer; and
treating the wafer surface to remove at least a portion of the dielectric layer with minimal removal of the photoresist layer, by applying an aqueous solution of one or more inorganic fluorine-comprising compounds and one or more organic acids in a ratio of about 1:2 (v/v), and having a pH of about 3 to about 9 such that the dielectric layer is removed selective to the photoresist at a rate of about 50 to about 1000 angstroms per minute.

16. The method of Claim 15, wherein the aqueous solution comprises at least hydrofluoric acid, and the dielectric layer is selectively removed at a rate of about 400 to about 600 angstroms per minute.

17. The method of Claim 15, wherein the aqueous solution comprises at least ammonium fluoride and the one or more organic acids in a ratio of about 2:1 (v/v), such that the dielectric layer is selectively removed at a rate of about 50 to about 150 angstroms per minute.

18. A post-etch cleaning to selectively remove a low-k dielectric material from a wafer, comprising:
providing a wafer surface having a layer of the low-k dielectric material disposed thereon and a photoresist layer overlying the dielectric layer; and

treating the wafer surface to remove at least a portion of the dielectric layer, by apply an aqueous solution of a least one inorganic fluorine-comprising compound and at least one organic acid component in a ratio of about 1:2 (v/v), the solution having a pH of about 3 to about 9, such that the removal rate of the low-k dielectric material is controlled at about 50 to about 1000 angstroms per minute.

19. A method of cleaning wafer surfaces, the method comprising the steps of:

providing an aqueous solution comprising at least one inorganic fluorine-comprising compound and at least one organic acid;

providing a wafer having an unmasked low-k dielectric material disposed on at least a portion of one surface; and

contacting the surface of the wafer having the low-k dielectric material thereon with the aqueous solution under conditions effective to remove at least a portion of the low-k dielectric material at a rate of greater than about 1000 angstroms per minute.

20. A method of cleaning wafer surfaces, the method comprising the steps of:

providing an aqueous solution comprising at least one inorganic fluorine-comprising compound selected from the group consisting of hydrofluoric acid and ammonium fluoride, and mixtures thereof; and at least one organic acid selected from the group consisting of citric acid, acetic acid, ascorbic acid, and mixtures thereof;

providing a wafer having a low-k dielectric material disposed on at least a portion of one surface; and

contacting the surface of the wafer having the low-k dielectric material thereon with the aqueous solution under conditions effective to remove at least a portion of the low-k dielectric material at a rate of about 50 to about 1000 angstroms per minute.

21. The method of Claim 20, wherein the aqueous solution comprises about 30 % to about 70 % by volume of the fluorine-comprising compound, and about 30 % to about 70 % by volume of the organic acid, based on the total volume of the solution.

22. The method of Claim 20, wherein the aqueous solution includes at least hydrofluoric acid and at least one organic acid in a ratio of about 1:2 (v/v), to remove at least a portion of the low-k material at a rate of about 400 to about 600 angstroms per minute.

23. The method of Claim 22, wherein the aqueous solution includes about 30 to about 40 % by volume of hydrofluoric acid, and about 60 to about 70 % by volume of the organic acid.

24. The method of Claim 20, wherein the aqueous solution includes at least ammonium fluoride and at least one organic acid in a ratio of about 2:1 (v/v), to remove at least a portion of the low-k material at a rate of about 50 to about 150 angstroms per minute.

25. The method of Claim 24, wherein the aqueous solution includes about 60 to about 70 % by volume of ammonium fluoride, and about 30 to about 40 % by volume of the organic acid.

26. A method of cleaning wafer surfaces, the method comprising the steps of:
providing an aqueous solution comprising an inorganic fluorine-comprising compound selected from the group consisting of hydrofluoric acid and ammonium fluoride, and mixtures thereof; and an organic acid selected from the group consisting of citric acid, acetic acid, ascorbic acid, and mixtures thereof;

providing a wafer having a low-k dielectric material disposed on at least a portion of one surface; and

contacting the surface of the wafer having the low-k dielectric material thereon with the aqueous solution under conditions effective to remove at least a portion of the low-k dielectric material at a rate greater than about 1000 angstroms per minute.

27. The method of Claim 26, wherein the aqueous solution includes at least hydrofluoric acid and one or more organic acids in a ratio of about 2:1 (v/v).

28. The method of Claim 27, wherein the aqueous solution includes about 63 to about 70 % by volume of hydrofluoric acid, and about 30 to about 36 % by volume of the one or more organic acids.

29. The method of Claim 26, wherein the aqueous solution includes at least ammonium fluoride and one or more organic acids in a ratio of about 2:1 (v/v).

30. The method of Claim 26, wherein the aqueous solution includes about 63 to about 70 % by volume of ammonium fluoride, and about 30 to about 36 % by volume of the one or more organic acids.

31. A method of surface treating wafer surfaces, comprising the steps of:
providing a wafer surface having a low-k dielectric layer disposed thereon and a photoresist layer overlying the dielectric layer; and
providing an aqueous composition comprising at least one inorganic fluorine-comprising compound, and a major amount of one or more organic acids; and
contacting the surface of the wafer having the low-k dielectric and photoresist layers thereon with the composition under conditions effective to selectively remove the photoresist layer while leaving the low-k layer essentially intact on the substrate.

32. The method of Claim 31, wherein the composition comprises an aqueous solution of at least hydrofluoric acid and the one or more organic acids in a ratio of about 1:100 to about 45:55 (v/v), such that the composition removes the photoresist mask completely from the surface selective to the dielectric layer.

33. The method of Claim 31, wherein the inorganic fluorine-comprising compound is selected from the group consisting of hydrofluoric acid, ammonium fluoride, and mixtures thereof; and the organic acid is selected from the group consisting of citric acid, gallic acid, acetic acid, formic acid, propionic acid, n-butyric acid, isobutyric acid, benzoic acid, ascorbic

acid, gluconic acid, malic acid, malonic acid, oxalic acid, succinic acid, tartaric acid, and mixtures thereof.

34. The method of Claim 31, wherein the organic acid is selected from the group consisting of citric acid, acetic acid, ascorbic acid, and mixtures thereof.

35. The method of Claim 31, wherein the step of contacting the surface of the wafer comprises immersing the wafer in a bath of the composition, spraying the surface of the wafer with the composition, exposing the wafer to a vapor, or any combination thereof.

36. A method of cleaning wafer surfaces, comprising:

formulating an aqueous composition for selectively removing at least a portion of a low-k dielectric layer from a wafer surface at a predetermined rate, the composition consisting essentially of one or more inorganic fluorine-comprising compounds and one or more organic acids, and having a pH of about 3 to about 9;

providing a wafer having a low-k dielectric material disposed on at least a portion of one surface; and

contacting the wafer having the low-k dielectric material thereon with the composition under conditions effective to remove at least a portion of the low-k dielectric material at the predetermined rate.

37. The method of Claim 36, wherein the inorganic fluorine-comprising compound is selected from the group consisting of hydrofluoric acid, ammonium fluoride, and mixtures thereof; and the organic acid is selected from the group consisting of citric acid, acetic acid, ascorbic acid, and mixtures thereof.

38. The method of Claim 36, wherein the composition is formulated to remove the dielectric layer at a rate greater than about 1000 angstroms per minute.

39. The method of Claim 36, wherein the composition is formulated to remove the dielectric layer at a rate of about 50 to about 1000 angstroms per minute.

40. The method of Claim 36, wherein at least a portion of the low-k dielectric layer is unmasked.

41. The method of Claim 36, wherein at least a portion of the low-k dielectric layer is masked by an overlying layer of photoresist.

42. The method of Claim 41, wherein the composition is formulated to remove the dielectric layer and the photoresist layer from the surface of the wafer, such that the surface of the substrate is rendered substantially hydrophobic.

43. The method of Claim 41, wherein the composition is formulated to remove the dielectric layer selective to the photoresist at a rate of about 50 to about 1000 angstroms per minute.

44. The method of Claim 41, wherein the composition is formulated to remove the dielectric layer selective to the photoresist at a rate of greater than about 1000 angstroms per minute.

45. A method of cleaning wafer surfaces, comprising:

formulating an aqueous composition for selectively removing at least a portion of a low-k dielectric layer disposed on the wafer surface at a predetermined rate, the composition consisting essentially of one or more organic fluorine-comprising compounds and one or more inorganic acids, and having a pH of about 3 to about 9;

providing a wafer having a low-k dielectric material disposed on at least a portion of one surface; and

contacting the wafer having the low-k dielectric material thereon with the composition under conditions effective to remove at least a portion of the low-k dielectric material at the predetermined rate.

46. The method of Claim 45, wherein the organic fluorine-comprising compound is selected from the group consisting of hydrogen fluoride pyridinium, triethylamine trihydrofluoride, tetramethylammonium fluoride, and mixtures thereof.

47. The method of Claim 45, wherein the inorganic acid is selected from the group consisting of sulfuric acid, nitric acid, hydrochloric acid, phosphoric acid, and mixtures thereof.

48. The method of Claim 45, wherein the composition is formulated to remove the dielectric layer at a rate greater than about 1000 angstroms per minute.

49. The method of Claim 45, wherein the composition is formulated to remove the dielectric layer at a rate of about 50 to about 1000 angstroms per minute.

50. The method of Claim 45, wherein at least a portion of the low-k dielectric layer is unmasked.

51. The method of Claim 45, wherein at least a portion of the low-k dielectric material is masked by an overlying layer of photoresist.

52. The method of Claim 51, wherein the composition is formulated to remove the dielectric layer and the photoresist layer from the surface of the wafer such that the surface of the substrate is rendered substantially hydrophobic.

53. The method of Claim 51, wherein the composition is formulated to remove the dielectric layer selective to the photoresist at a rate of about 50 to about 1000 angstroms per minute.

53. The method of Claim 51, wherein the composition is formulated to remove the dielectric layer selective to the photoresist at a rate of greater than about 1000 angstroms per minute.

54. A composition for cleaning or treating a surface of a semiconductor wafer, comprising:
an aqueous solution of a major amount of one or more inorganic fluorine-comprising
compounds and one or more organic acids in a ratio of about 100:1 to about 55:45 (v/v), to
remove organic material and low-k dielectric material from the surface of the wafer whereby the
surface of the substrate is rendered substantially hydrophobic; the composition having a pH of
about 3 to about 9.

55. The composition of Claim 54, wherein the inorganic fluorine-comprising compound is
selected from the group consisting of hydrofluoric acid, ammonium fluoride, and mixtures
thereof.

56. The composition of Claim 54, wherein the organic acid is selected from the group
consisting of citric acid, gallic acid, acetic acid, formic acid, propionic acid, n-butyric acid,
isobutyric acid, benzoic acid, ascorbic acid, gluconic acid, malic acid, malonic acid, oxalic acid,
succinic acid, tartaric acid, and mixtures thereof.

57. The composition of Claim 54, wherein the organic acid is selected from the group
consisting of citric acid, acetic acid, ascorbic acid, and mixtures thereof.

58. The composition of Claim 54, wherein the aqueous solution consists essentially of the
one or more inorganic fluorine-comprising compounds and the one or more organic acids.

59. The composition of Claim 54, wherein the aqueous solution includes at least hydrofluoric
acid and at least one organic acid in a ratio of about 1:2 (v/v).

60. The composition of Claim 59, wherein the aqueous solution includes about 30 to about
40 % by volume of hydrofluoric acid, and about 60 to about 70 % by volume of the organic acid.

61. The composition of Claim 54, wherein the aqueous solution includes at least ammonium fluoride and at least one organic acid in a ratio of about 2:1 (v/v).

62. The composition of Claim 61, wherein the aqueous solution includes about 60 to about 70 % by volume of ammonium fluoride, and about 30 to 40 % by volume of the organic acid.

63. A composition for cleaning or treating a surface of a semiconductor wafer, comprising:
an aqueous solution of a major amount of one or more organic fluorine-comprising compounds and one or more inorganic acids in a ratio of about 1:5 (v/v), to remove organic material and low-k dielectric material from the surface of the wafer such that the surface of the substrate is rendered substantially hydrophobic; the composition having a pH of about 3 to about 9.

64. The composition of Claim 63, wherein the organic fluorine-comprising compound is selected from the group consisting of hydrogen fluoride pyridinium, tetramethylammonium fluoride, triethylamine trihydrofluoride, and mixtures thereof.

65. The composition of Claim 63, wherein the inorganic acid is selected from the group consisting of sulfuric acid, nitric acid, hydrochloric acid, phosphoric acid, and mixtures thereof.

66. The composition of Claim 63, wherein the aqueous solution consists essentially of the one or more organic fluorine-comprising compounds and the one or more inorganic acids.

67. A composition for surface treating wafer surfaces, comprising:
an aqueous solution of a major amount of one or more inorganic fluorine-comprising compounds and one or more organic acids to remove organic material and low-k dielectric material from the surface of the wafer, such that the dielectric layer is removed selective to the photoresist at a rate of about 50 to about 1000 angstroms per minute; the composition having a pH of about 3 to about 9.

68. The composition of Claim 67, wherein the aqueous solution comprises at least hydrofluoric acid, and the dielectric layer is selectively removed at a rate of about 400 to about 600 angstroms per minute.

69. The composition of Claim 67, wherein the aqueous solution comprises at least ammonium fluoride and the one or more organic acids in a ratio of about 2:1 (v/v), such that the dielectric layer is selectively removed at a rate of about 50 to about 150 angstroms per minute.

70. The composition of Claim 67, wherein the composition is an aqueous solution consisting essentially of the one or more inorganic fluorine-comprising compounds and the one or more organic acids.

71. A composition for surface treating wafer surfaces, comprising:
an aqueous solution of a major amount of one or more inorganic fluorine-comprising compounds and one or more organic acids to remove organic material and low-k dielectric material from the surface of the wafer, such that the dielectric layer is removed selective to the photoresist at a rate up to than about 1000 angstroms per minute; the composition having a pH of about 3 to about 9.

72. The composition of Claim 71, wherein the aqueous solution comprises at least hydrofluoric acid and the one or more organic acids in a ratio of about 1:2 (v/v), whereby the dielectric layer is selectively removed at a rate of about 400 to about 600 angstroms per minute.

73. The composition of Claim 71, wherein the aqueous solution comprises at least ammonium fluoride and the one or more organic acids in a ratio of about 2:1 (v/v), whereby the dielectric layer is selectively removed at a rate of about 50 to about 150 angstroms per minute.

74. The composition of Claim 71, wherein the composition is an aqueous solution consisting essentially of the one or more inorganic fluorine-comprising compounds and the one or more organic acids.

ABSTRACT

An improved composition and method for cleaning the surface of a semiconductor wafer are provided. The composition can be used to selectively remove a low-k dielectric material such as silicon dioxide, a photoresist layer overlying a low-k dielectric layer, or both layers from the surface of a wafer. The composition is formulated according to the invention to provide a desired removal rate of the low-k dielectric and/or photoresist from the surface of the wafer. By varying the fluorine ion component, and the amounts of the fluorine ion component and acid, component, and controlling the pH, a composition can be formulated in order to achieve a desired low-k dielectric removal rate that ranges from slow and controlled at about 50 to about 1000 angstroms per minute, to a relatively rapid removal of low-k dielectric material at greater than about 1000 angstroms per minute. The composition can also be formulated to selectively remove a photoresist layer, leaving the underlying low-k dielectric layer essentially intact.

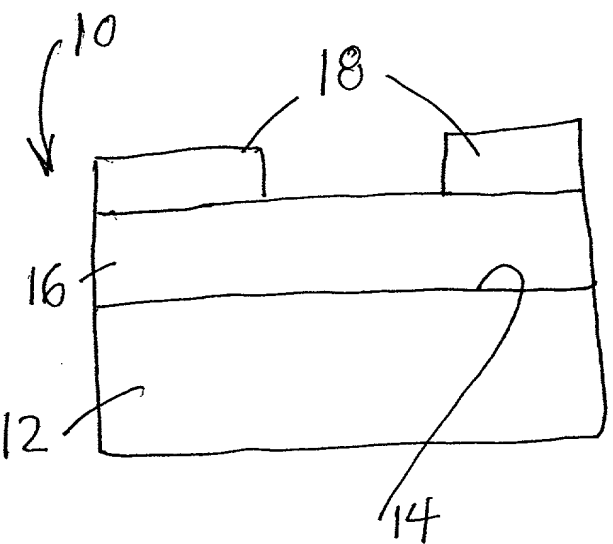


FIG. 1A

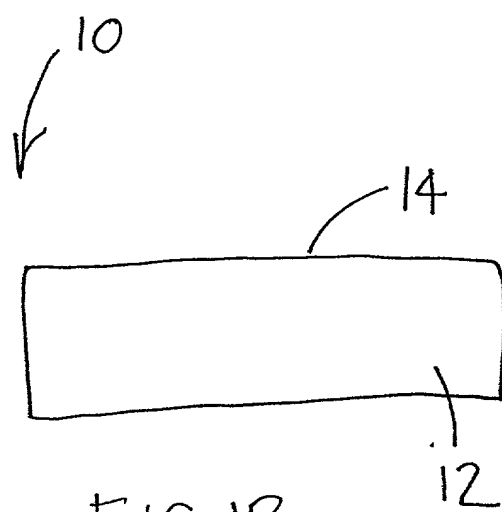


FIG. 1B

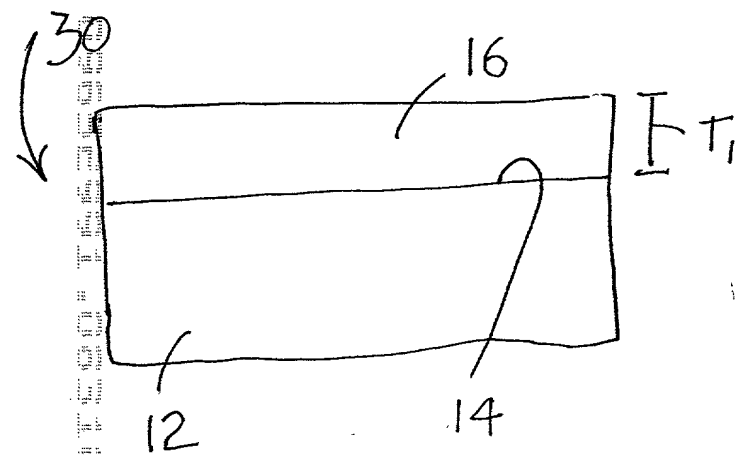


FIG. 2A

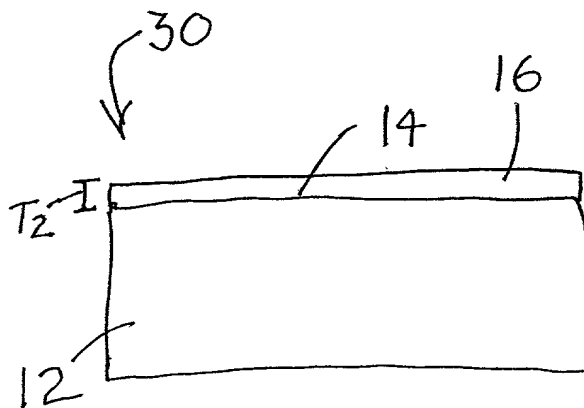


FIG. 2B

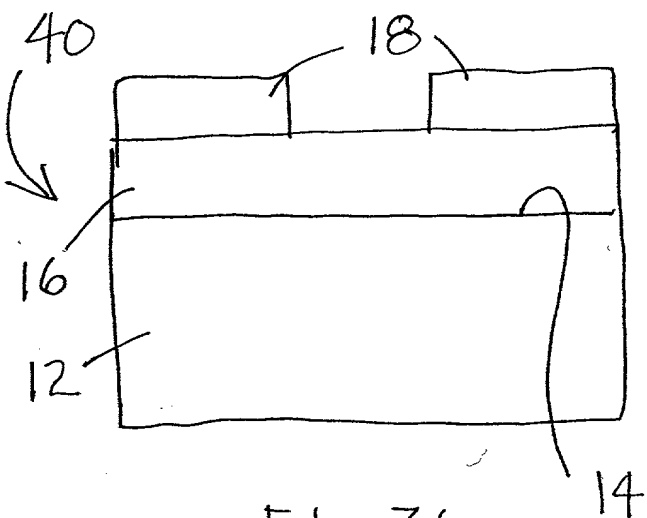


FIG. 3A

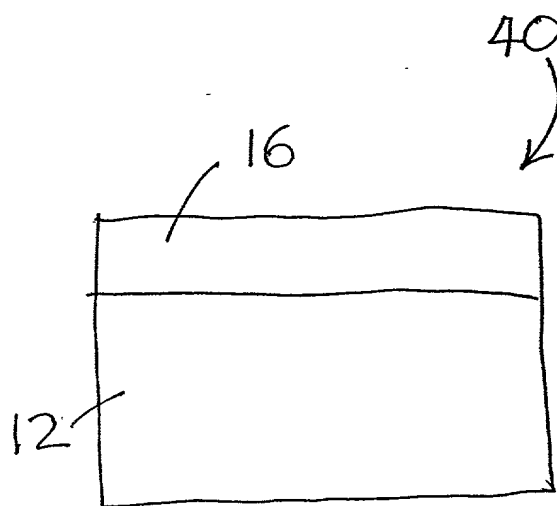


FIG. 3B

Please type a plus sign (+) inside this box → ☐

PTO/SB/01 (12-97)

Approved for use through 9/30/00. OMB 0651-0032

Patent and Trademark Office; U.S. DEPARTMENT OF COMMERCE

Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it contains a valid OMB control number.

DECLARATION FOR UTILITY OR DESIGN PATENT APPLICATION (37 CFR 1.63)	Attorney Docket Number	MTI-31046
	First Named Inventor	Yates, Donald L.
	COMPLETE IF KNOWN	
	Application Number	
	Filing Date	
	Group Art Unit	
<input checked="" type="checkbox"/> Declaration Submitted with Initial Filing	OR	<input type="checkbox"/> Declaration Submitted after Initial Filing (surcharge (37 CFR 1.16 (e)) required)
	Examiner Name	

As a below named inventor, I hereby declare that:

My residence, post office address, and citizenship are as stated below next to my name.

I believe I am the original, first and sole inventor (if only one name is listed below) or an original, first and joint inventor (if plural names are listed below) of the subject matter which is claimed and for which a patent is sought on the invention entitled:

Compositions for Dissolution of Low-K Dielectric Films, and Methods of Use

the specification of which

(Title of the Invention)

☒ is attached hereto
OR☐ was filed on (MM/DD/YYYY) as United States Application Number or PCT InternationalApplication Number and was amended on (MM/DD/YYYY) (if applicable).

I hereby state that I have reviewed and understand the contents of the above identified specification, including the claims, as amended by any amendment specifically referred to above.

I acknowledge the duty to disclose information which is material to patentability as defined in 37 CFR 1.56.

I hereby claim foreign priority benefits under 35 U.S.C. 119(a)-(d) or 356(b) of any foreign application(s) for patent or inventor's certificate, or 356(a) of any PCT international application which designated at least one country other than the United States of America, listed below and have also identified below, by checking the box, any foreign application for patent or inventor's certificate, or of any PCT international application having a filing date before that of the application on which priority is claimed.

Prior Foreign Application Number(s)	Country	Foreign Filing Date (MM/DD/YYYY)	Priority Not Claimed	Certified Copy Attached?	
				YES	NO
			<input type="checkbox"/>	<input type="checkbox"/>	<input type="checkbox"/>
			<input type="checkbox"/>	<input type="checkbox"/>	<input type="checkbox"/>
			<input type="checkbox"/>	<input type="checkbox"/>	<input type="checkbox"/>
			<input type="checkbox"/>	<input type="checkbox"/>	<input type="checkbox"/>

☐ Additional foreign application numbers are listed on a supplemental priority data sheet PTO/SB/02B attached hereto:

I hereby claim the benefit under 35 U.S.C. 119(e) of any United States provisional application(s) listed below.

Application Number(s)	Filing Date (MM/DD/YYYY)	<input type="checkbox"/> Additional provisional application numbers are listed on a supplemental priority data sheet PTO/SB/02B attached hereto.

[Page 1 of 2]

Burden Hour Statement: This form is estimated to take 0.4 hours to complete. Time will vary depending upon the needs of the individual case. Any comments on the amount of time you are required to complete this form should be sent to the Chief Information Officer, Patent and Trademark Office, Washington, DC 20231. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Assistant Commissioner for Patents, Washington, DC 20231.

Please type a plus sign (+) inside this box → ☐

PTO/SB/01 (12-97)

Approved for use through 9/30/00. OMB 0651-0032

Patent and Trademark Office; U.S. DEPARTMENT OF COMMERCE

Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it contains a valid OMB control number.

DECLARATION — Utility or Design Patent Application

I hereby claim the benefit under 35 U.S.C. 120 of any United States application(s), or 365(c) of any PCT international application designating the United States of America, listed below and, insofar as the subject matter of each of the claims of this application is not disclosed in the prior United States or PCT International application in the manner provided by the first paragraph of 35 U.S.C. 112, I acknowledge the duty to disclose information which is material to patentability as defined in 37 CFR 1.56 which became available between the filing date of the prior application and the national or PCT international filing date of this application.

U.S. Parent Application or PCT Parent Number	Parent Filing Date (MM/DD/YYYY)	Parent Patent Number (if applicable)

☐ Additional U.S. or PCT international application numbers are listed on a supplemental priority data sheet PTO/SB/02C attached hereto.

As a named inventor, I hereby appoint the following registered practitioner(s) to prosecute this application and to transact all business in the Patent and Trademark Office connected therewith:

☐ Customer Number 022202

OR

☒ Registered practitioner(s) name/registration number listed below

Place Customer Number Bar Code Label here

Name	Registration Number	Name	Registration Number
Gary R. Plotecher	27830	Alan E. Wagner	45188
Kristine M. Strodthoff	34259	Thomas J. Pienkos	P46992
Alexander R. Kuszewski	41920	Michael L. Lynch	30871

☒ Additional registered practitioner(s) named on supplemental Registered Practitioner Information sheet PTO/SB/02C attached hereto.Direct all correspondence to: ☐ Customer Number or Bar Code Label ☒ Correspondence address below

Name	Kristine M. Strodthoff, Esq		
Address	Whyte Hirschboeck Dudek S.C.		
Address	111 E. Wisconsin Avenue, Suite 2100		
City	Milwaukee	State	WI
		ZIP	53202
Country		Telephone	414-273-2100
		Fax	414-223-5000

I hereby declare that all statements made herein of my own knowledge are true and that all statements made on information and belief are believed to be true; and further that these statements were made with the knowledge that willful false statements and the like so made are punishable by fine or imprisonment, or both, under 18 U.S.C. 1001 and that such willful false statements may jeopardize the validity of the application or any patent issued thereon.

Name of Sole or First Inventor: ☐ A petition has been filed for this unsigned inventor

Given Name (first and middle [if any])		Family Name or Surname	
Donald L.		Yates	
Inventor's Signature	Date		8/30/00
Residence: City	Boise	State	ID
		Country	USA
		Citizenship	USA
Post Office Address	11151 Musket Street		
Post Office Address			
City	Boise	State	ID
		ZIP	83713
		Country	USA

☐ Additional inventors are being named on the 1 supplemental Additional Inventor(s) sheet(s) PTO/SB/02A attached hereto

Patent

Attorney Docket No. MTI-31046

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Yates, Donald L.
Serial No. : Not Yet Assigned
Filing Date :
For : Compositions for Dissolution of Low-K Dielectric Films, and
Methods of Use

Assistant Commissioner for Patents
Washington, D.C. 20231

**POWER OF ATTORNEY BY ASSIGNEE
AND CERTIFICATE UNDER 37 CFR § 3.73(b)**

Sir:

MICRON TECHNOLOGY, INC., assignee of the entire right, title and interest by assignment from the inventor(s) in the above-identified application, hereby appoints the following attorneys and agents:

Gary R. Plotecher, Reg. No. 27830
Alan E. Wagner, Reg. No. 45188
Alexander R. Kuszewski, Reg. No. 41920
Charles B. Brantley, II, Reg. No. 38086

Kristine M. Strodthoff, Reg. No. 34259
Thomas J. Pienkos, Reg. No. P46992
Michael L. Lynch, Reg. No. 30871

as its attorneys with full power of substitution to prosecute this application and all applications claiming filing date priority therefrom and to transact all business in the U.S. Patent and Trademark Office in connection therewith.

The above-identified assignee hereby elects, pursuant to 37 CFR §3.71, to conduct the prosecution of the above-identified patent application to the exclusion of the inventor(s).

A chain of title from the inventor(s) of the above-identified patent application to the above-identified assignee is shown:

- ☐ In an assignment recorded in the U.S. Patent and Trademark Office at Reel ___, Frame ____.
- ☒ In an assignment filed herewith for recordation, a true copy of which is attached hereto.

The undersigned has reviewed the above-identified assignment and, to the best of his knowledge and belief, title is in the above-identified assignee.

614962.1

Page 1 of 2

The undersigned further avers that he is empowered to make and sign the foregoing certification on behalf of the above-identified assignee, and to take the action set further herein on its behalf.

Please direct all communications regarding the above-identified application to:

Kristine M. Strodthoff
Whyte Hirschboeck Dudek S.C.
111 E. Wisconsin Ave., Suite 2100
Milwaukee, WI 53202
phone: (414) 273-2100
fax: (414) 223-5000

Respectfully submitted,

MICRON TECHNOLOGY, INC.

Dated: _____

By: _____
Michael L. Lynch
Chief Patent Counsel